



ELSEVIER

Contents lists available at [ScienceDirect](http://ScienceDirect.com)

Journal of Solid State Chemistry

journal homepage: www.elsevier.com/locate/jsscStructural and electronic properties of Li-ion battery cathode material MoF₃ from first-principlesA.Y. Li^a, S.Q. Wu^b, Y. Yang^c, Z.Z. Zhu^{b,d,*}^a School of Opto-electronic and Communication Engineering, Xiamen University of Technology, Xiamen 361024, China^b Department of Physics and Institute of Theoretical Physics and Astrophysics, Xiamen University, Xiamen 361005, China^c State Key Lab for Physical Chemistry of Solid Surfaces, Xiamen University, Xiamen 361005, China^d Fujian Provincial Key Laboratory of Theoretical and Computational Chemistry, Xiamen University, Xiamen 361005, China

ARTICLE INFO

Article history:

Received 20 January 2015

Received in revised form

6 March 2015

Accepted 18 March 2015

Available online 27 March 2015

Keywords:

MoF₃

Electronic structures

Magnetism

First-principles

ABSTRACT

The transition metal fluorides have been extensively investigated recently as the electrode materials with high working voltage and large capacity. The structural, electronic and magnetic properties of MoF₃ are studied by the first-principles calculations within both the generalized gradient approximation (GGA) and GGA+U frameworks. Our results show that the antiferromagnetic configuration of MoF₃ is more stable than the ferromagnetic one, which is consistent with experimental results. The analysis of the electronic density of states shows that MoF₃ is a Mott–Hubbard insulator with a *d–d* type band gap, which is similar to the case of FeF₃. Moreover, small spin polarizations were found on the sites of fluorine ions, which accords with a fluorine-mediated superexchange mechanism for the Mo–Mo magnetic interaction.

© 2015 Elsevier Inc. All rights reserved.

1. Introduction

Lithium-ion batteries (LIBs) have undergone widely scientific research and shown successful commercial applications in a variety of portable electronic devices and electric vehicles [1,2]. At present, LiCoO₂ is utilized as a cathode in most of the commercial lithium ion batteries [3,4], however, the active reversible specific capacity of LiCoO₂ is below 150 mA h g⁻¹ which cannot well meet the requirement of the power lithium ion battery. To satisfy the demand for the electric vehicles, much attention has been paid to the development of new systems, in particular to those with high energy density and discharge voltage which can store more energy at reduced weight [5–11]. In a way, the choice of cathode materials is very important. Good cathode material can accommodate a large amount of Li-ions, which can supply high capacity. Recently, as a special class of promising cathode materials, transition metal fluorides have attracted great interest due to high ionicity which can provide high operating voltage in Li-ion batteries [12–15]. Metal fluorides enable the highest specific capacity via the large multi-electron reversible

redox conversion process through the following reaction scheme:



However, the highly ionic nature of M–F bond leads to an insulating character of MF with poor electronic conductivity and limits their discharge voltage. For example, the discharge capacity of FeF₃ (80 mA h g⁻¹) first reported by Arai et al. [16] is far below the theoretical 1e⁻ transfer reaction capacity of the Fe³⁺/Fe²⁺ couple (237 mA h g⁻¹). Fortunately, electronic limitations are no longer an insurmountable issue in design of high-performance electrode material. Low conductivity can be improved through various materials processing approaches, including the use of carbon coatings, mechanical grinding, mixing [17], and low-temperature synthesis routes [14] to obtain tailored particles. Among transition metal fluorides, FeF₃, CuF₂ [18] are widely investigated, however, little has been done on MoF₃. As is well known, molybdenum is a multi-valence-electron element which could enable a six-electron reversible process resulting in specific high capacities. Therefore, element Mo has been very active in the field of lithium ion batteries. Molybdenum disulfide and molybdenum oxide are well-known lithium insertion compounds and have been much investigated [19,20]. Moreover, experiments [21] have shown that MoF₃ and FeF₃ have the same crystal structure and magnetic structure. The magnetic ground state of MoF₃ or FeF₃ is antiferromagnetism (AFM), in which each metal atom is antiferromagnetically coupled through the intervening fluorine atoms to each of its six nearest neighbors. Consequently, it is of great interest to explore and understand the intrinsic structural properties and electronic characteristics of

* Corresponding author at: Fujian Provincial Key Laboratory of Theoretical and Computational Chemistry, Xiamen University, Xiamen 361005, China. Tel.: +86 592 2182248; fax: +86 592 2189426.

E-mail address: zzhu@xmu.edu.cn (Z.Z. Zhu).

the MoF₃ material. In this paper, we focus on the study of ground state properties of MoF₃, by analyzing the structural, magnetic, and electronic properties from first-principles calculations.

The present calculations have been performed by using the Vienna ab initio simulation package (VASP) [22,23], which is based on the density functional theory, the plane-wave basis, and the projector augmented wave (PAW) representation [24]. The exchange correlation potentials are approximated by the generalized gradient-corrected approximation (GGA) [25]. To address the on-site Coulomb interactions in the localized *d* electrons of Mo ions, the GGA+U method with an additional Hubbard-type U term [26] was employed. Here, an $U_{\text{eff}}=U-J=2$ eV is used in this paper. In the study of magnetism of MoO₂, Wang et al. [27] used a range of values for U_{eff} between 1 and -1 eV, citing weak correlations in Mo. Jain and Hautier [28] more accurately predicted the formation enthalpies of 49 ternary oxides by mixing GGA and GGA+U energies, they arrived at a value of $U_{\text{eff}}=3.5$ for Mo. Saitoh et al. [29] suggested a value of $U_{\text{eff}}=1.0$ for Mo based on a comparison of the computed band structure with valence-band photoemission spectra of single crystals of Sr₂FeMoO₆. We, therefore, take an average value of $U_{\text{eff}}=2.0$ eV. The wave functions were expanded in plane-wave basis up to a kinetic energy cutoff of 500 eV. Brillouin-zone integrations were performed by using special *k*-point sampling of the Monkhorst–Pack

scheme [30] with a $4 \times 4 \times 2$ grid. The convergence of total energy with respect to the kinetic energy cutoff and the *k*-point sampling has been examined. The atomic geometry of MoF₃ was fully relaxed until the Hellmann–Feynman forces on all atoms were less than $0.01 \text{ eV } \text{Å}^{-1}$. The unit cell adopted for the present calculation contains 6 formula unit of MoF₃, which is 24 atom per unit cell (18 fluorine atoms and 6 Mo atoms).

Several experimental studies [21,31] have shown that MoF₃ has a bimolecular rhombohedral unit cell of space group $R\bar{3}c$. The hexagonal representation of the lattice, as shown in Fig. 1, is related to a collapsed ReO₃ perovskite structure. The Mo–F–Mo bond angle is deviated from the ideal 180° (experimental value of 141.02° [31]). MoF₃ also exhibits a layered structure and comprises corner-sharing MoF_{6/2} octahedra. In Table 1, we have presented the calculated lattice parameters, the bond length of Mo–F, the bond angle of Mo–F–Mo and the spin magnetic moments of Mo and F ions in MoF₃. Both of the GGA and GGA+U calculations predict that the AFM configuration is more favorable. The differences of cohesive energies (per molecular formula) between antiferromagnetic and ferromagnetic configurations are 0.476 eV for GGA and 0.234 eV for GGA+U calculations, respectively. Their lattice parameters calculated within the GGA+U scheme are larger than those calculated within the GGA.

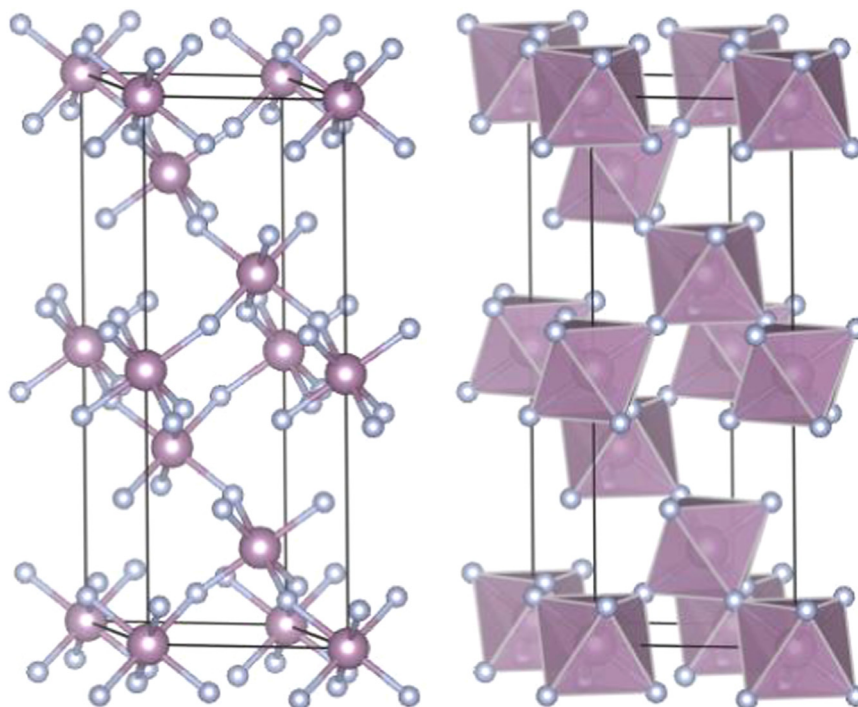


Fig. 1. The crystal structure of MoF₃ in the hexagonal structure. The Mo and F atoms are denoted by larger and smaller balls, respectively. Mo–F₆ octahedra are also shown in the right panel.

Table 1
The optimized lattice parameters, the cohesive energies E_c (in eV/molecular formula), the Mo–F bond lengths, the bond angles of Mo–F–Mo, and the magnetic moments of Mo and F ions of MoF₃ for the FM and AFM configurations calculated by both the GGA and GGA+U schemes, together with the experimental data [31].

Method	a (Å)	c (Å)	E_c (eV)	$R_{\text{Mo-F}}$ (error) (Å)	$\angle\text{Mo-F-Mo}$ (°)	m (Mo) (μB)	m (F) (μB)
AFM [31]	5.213	14.41	–	2.04	141.02		
FM: GGA	5.276	14.492	152.098	2.07 (1.4%)	139.37	2.689	0.054
FM: GGA+U	5.410	14.782	145.350	2.08 (1.9%)	139.80	3.053	0.021
AFM: GGA	5.388	14.395	152.574	2.06 (0.9%)	145.10	2.513	0
AFM: GGA+U	5.386	14.557	145.584	2.08 (1.9%)	143.16	2.721	0

Experiments show that MoF₃ is an insulator, and its magnetic susceptibility is of temperature dependence which reveals the antiferromagnetic character of this compound [21]. These measurements also attribute a Néel temperature of 185 K to MoF₃. To gain further insight into the electronic structure of MoF₃, the total density of states (TDOS) in the antiferromagnetic configuration calculated by GGA+U scheme, together with the Mo-4d and F-2p partial density of states (PDOS), has been shown in Fig. 2. The TDOS of AFM-MoF₃ is shown to be divided into several regions. The peak around -3.5 eV is of mainly F-2p character. In the energy region below -4.8 eV, the TDOS shows significant contributions from both the Mo-4d and F-2p states, i.e., showing a strong hybridization of Mo-4d and F-2p atomic orbitals. A narrow band located at -0.5 to 0.0 eV are from the Mo-4d orbital. For the conduction bands (around 3 to 5 eV), the contributions are also almost fully from the Mo-4d orbital.

In order to comprehend the electronic properties of MoF₃ more clearly, the DOS for the ferromagnetic configuration is also calculated by both the GGA and GGA+U methods, and results are presented in Fig. 3 for comparison. Fig. 3 suggests that the electronic structures for both the AFM and FM configurations predicted by the GGA method are similar to those by the GGA+U scheme, in addition to the values of band gaps. The GGA calculations predicted a semiconductor character for MoF₃ with band gaps of 1.42 eV for AFM and 0.87 eV for FM, respectively. However, GGA+U calculations indicated that MoF₃ is an insulator with band gaps of 2.59 eV for AFM and 1.92 eV for FM configurations, respectively. Obviously, GGA+U calculations show better size of band gap for MoF₃. Because of the well-known band-gap problem

in the density functional theory, the size of the band gap should be well underestimated by the GGA method. The wide energy gap of MoF₃ results in poor electronic conductivity which might likely restrict the application of MoF₃ as cathode materials. However, electronic conductivity limitation might be overcome through several materials processing approaches, including the use of carbon coating, mechanical grinding or mixing, and low-temperature synthesis routes to obtain tailored particles. From Fig. 3, it is also shown that the DOS peaks at valence-band maximum and conduction-band minimum for AFM states are much more localized than those of FM ones, from both the GGA and GGA+U calculations. Since the valence-conduction band gap is separated by Mo-d states, MoF₃ is then a Mott-Hubbard insulator like FeF₃ and FeF₂ [32,33], rather than a charge-transfer insulator.

To visualize the nature of the bond character, to explain the charge transfer and the bonding properties of MoF₃, the deformation charge density plot for the plane containing two F-Mo bonds of MoF₃ is shown in Fig. 4(a). The deformation charge density, $\Delta\rho(\vec{r})$, is defined as the difference between the total charge density in the solid and the superposition of independent atomic charge densities placed at the atomic sites of the same solid, i.e.,

$$\Delta\rho(\vec{r}) = \rho(\vec{r}) - \sum_{\mu} \rho_{\text{atom}}(\vec{r} - \vec{R}_{\mu})$$

where \vec{R}_{μ} are the atomic coordinates. Only the results from GGA+U approach in the AFM configuration is presented in Fig. 4(a), because GGA method presents similar maps for the deformation charge

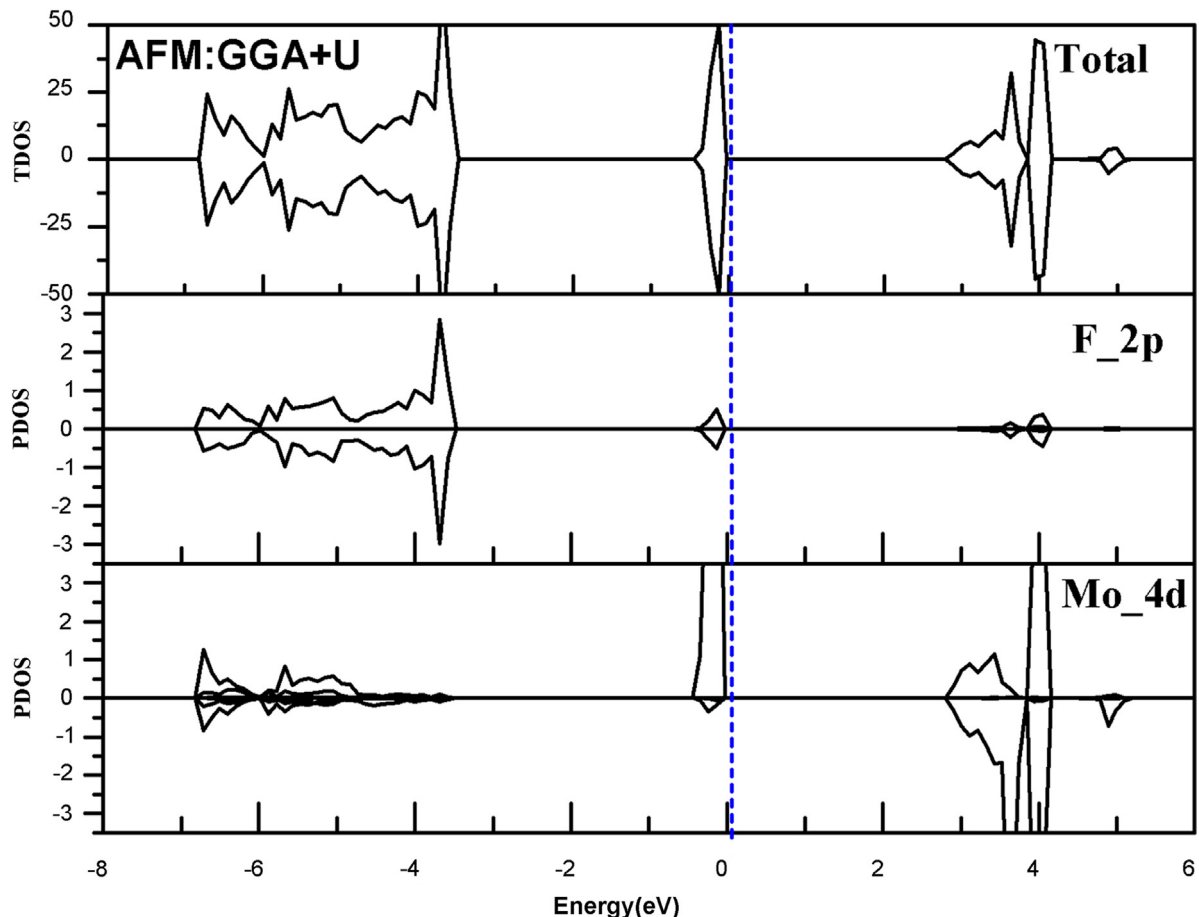


Fig. 2. The spin-polarized total density of states (TDOS) for MoF₃ and partial density of states (PDOS) for F-2p and Mo-4d orbitals predicted by GGA+U method for antiferromagnetic state of MoF₃. The valence-band maximum is shown by the vertical dot line. The unit of TDOS is states/eV unit cell.

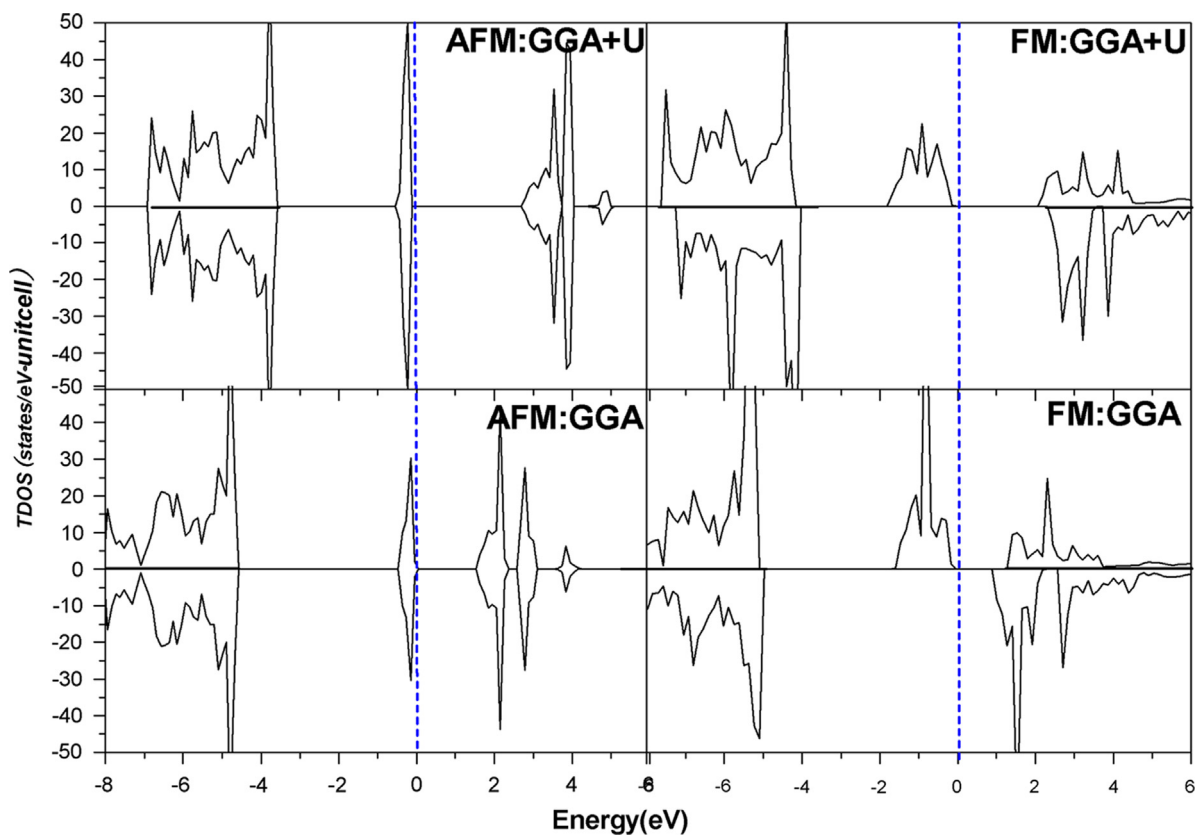


Fig. 3. The total density of states for the MoF₃ in the AFM and FM configurations calculated by both GGA+U and GGA schemes. The valence-band maximum is shown by the vertical dot line.

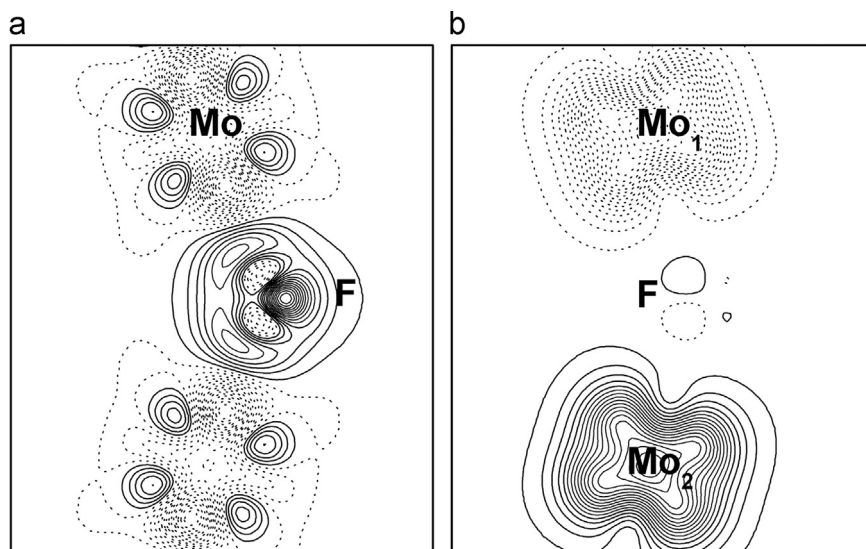


Fig. 4. Contour plots on the Mo–F–Mo plane of the (a) deformation charge density and (b) spin-density for MoF₃ in the AF configuration calculated with GGA+U scheme. Isodensity curves are separated by (a) 0.028 and (b) 0.061 e Å⁻³. Solid and dot dash lines correspond to positive and negative values, respectively.

density. The bonding between Mo and F shows prominent ionic characteristics as well as some covalency, in line with the high electronegativity of the F atom. Charge polarizability and dipole-dipole interactions have been proved as the major influences on the stabilization of tilts of corner coupled rigid octahedrons.

To further understand the magnetic properties, the calculated spin charge density plots (i.e., the spin-up charge density minus the spin-down one) for the AFM configuration from the GGA+U calculations is given in Fig. 4(b). The magnetism of MoF₃ is mainly expressed by Mo, as expected. As shown in Fig. 4(b), there is a net

excess of spin-down over spin-up electrons around the site of Mo₁, while the neighboring atoms of Mo₁, i.e., Mo₂, has a net spin-up electrons. The spin-up and spin-down electron distributions are almost identical, showing an AFM configuration in the ground state of MoF₃. Mo shows also remarkable high-spin magnetism. On the other hand, it is very interesting to remark that fluorine exhibits a small magnetism as well. On the sites of fluorine ions, a very small spin polarization is clearly visible in Fig. 4(b). Such spin polarizations on the sites of F ions are convincing evidence for the fluorine-mediated superexchange mechanism for the Mo–Mo

magnetic interaction. Similar effect of spin electron transfer and superexchange mechanism were discussed before in FeF₃ [32] and FeF₂ [33].

In summary, we have performed first-principles calculations based on the density functional theory within the GGA and GGA+U schemes to predict the structural properties and electronic structures of MoF₃ in both the ferromagnetic and antiferromagnetic states. Our results show that GGA+U approximation provided more reasonable predictions on the structural and electronic properties of MoF₃, in consideration of the strongly correlated 4d-electron orbitals of Mo atoms. By comparing cohesive energies in the AFM and FM configurations, the MoF₃ in AFM turns out to be more stable, consistent with experiments. The electronic structure calculations indicate that MoF₃ is an insulator with strong ionic character and a large band gap. Furthermore, analysis of the electronic density of states suggests that MoF₃ is a Mott–Hubbard insulator with a *d–d* type band gap. Moreover, small spin polarizations are found on the sites of F-ions, which is in agreement with a picture of fluorine-mediated superexchange mechanism for the Mo–Mo magnetic interaction.

Acknowledgments

This work is supported by the National Natural Science Foundation of China under Grant no. 21233004 and the Scientific Research Foundation of Fujian Provincial Education Department (Grant no. JK2011045).

References

- [1] M. Armand, J.M. Tarascon, *Nature* 451 (2008) 652.
- [2] J.M. Tarascon, M. Armand, *Nature* 414 (2001) 359.
- [3] J. Li, R. Klöpsch, M.C. Stan, S. Nowak, M. Kunze, et al., *J. Power Sources* 196 (2011) 4821.
- [4] C.Q. Zhu, C.H. Yang, W.D. Yang, C.Y. Hsieh, *J. Alloys Compd.* 496 (2010) 703.
- [5] R.B. Araujo, R.H. Scheicher, J.S. de Almeida, A.F. da Silva, R. Ahuja, *Solid State Commun.* 173 (2013) 9.
- [6] J.M. Wang, J.P. Hu, C.Y. Ouyang, S.Q. Shi, M.S. Lei, *Solid State Commun.* 151 (2011) 234.
- [7] Y. Yamada, T. Doi, I. Tanaka, S. Okada, J. Yamaki, *J. Power Sources* 196 (2011) 4837.
- [8] I. Bhaumik, S. Kumar, S. Ganesamoorthy, R. Bhatt, A.K. Karnal, B.N.R. Sekhar, *Solid State Commun.* 151 (2011) 1869.
- [9] H. Kim, D.J. Kim, D.H. Seo, M.S. Yeom, K. Kang, D.K. Kim, Y. Jung, *Chem. Mater.* 24 (2012) 1205.
- [10] H. Kim, R.A. Shakoor, C. Park, S.Y. Lim, J.S. Kim, K. Miyasaka, R. Kahraman, Y. Jung, J.W. Choi, *Adv. Funct. Mater.* 23 (2013) 1147.
- [11] Y. Zheng, P. Zhang, S.Q. Wu, Y.H. Wen, Z.Z. Zhu, Y. Yang, *J. Electrochem. Soc.* 160 (2012) A927.
- [12] M. Nishijima, I.D. Gocheva, S. Okada, T. Doi, J. Yamaki, T. Nishida, *J. Power Sources* 190 (2009) 558.
- [13] P. Liao, B.L. MacDonald, R.A. Dunlap, J.R. Dahn, *Chem. Mater.* 20 (2008) 454.
- [14] T. Li, L. Li, Y.L. Cao, X.P. Ai, H.X. Yang, *J. Phys. Chem. C* 114 (2010) 3190.
- [15] F. Badway, F. Cosandey, N. Pereira, G.G. Amatucci, *J. Electrochem. Soc.* 150 (2003) A1318.
- [16] H. Arai, S. Okada, Y. Sakurai, J. Yamaki, *J. Power Source* 68 (1997) 716.
- [17] F. Badway, N. Pereira, F. Cosandey, G.G. Amatucci, *J. Electrochem. Soc.* 150 (9) (2003) A1209.
- [18] A.N. Mansour, F. Badway, W.-S. Yoon, K.Y. Chung, G.G. Amatucci, *J. Solid State Chem.* 183 (2010) 3029.
- [19] G.D. Du, Z.P. Guo, S.Q. Wang, R. Zeng, Z.X. Chen, H.K. Liu, *Chem. Commun.* 46 (2010) 1106.
- [20] S.H. Lee, Y.H. Kim, R. Deshpande, A.C. Dillon, *Adv. Mater.* 20 (2008) 3627.
- [21] M.K. Wilkinson, E.O. Wollan, H.R. Child, J.W. Cable, *Phys. Rev.* 121 (1961) 74.
- [22] G. Kresse, J. Furthmüller, *Phys. Rev. B* 54 (1996) 11169.
- [23] G. Kresse, J. Furthmüller, *Comput. Mater. Sci.* 6 (1996) 15.
- [24] P. Blöchl, *Phys. Rev. B* 50 (1994) 17953.
- [25] J.P. Perdew, J.A. Chevary, S.H. Vosko, K.A. Jackson, M.R. Pederson, D.J. Singh, C. Fiolhais, *Phys. Rev. B* 46 (1992) 6671.
- [26] I.V. Solovyev, P.H. Dederichs, *Phys. Rev. B* 50 (1994) 16861.
- [27] F.G. Wang, Z.Y. Pang, L. Liang, S.H. Han, *Phys. Rev. B* 81 (2010) 134407.
- [28] A. Jain, G. Hautier, G. Ceder, *Phys. Rev. B* 84 (2011) 045115.
- [29] T. Saitoh, M. Nakatake, A. Kakizaki, *Phys. Rev. B* 66 (2002) 035112.
- [30] H.J. Monkhorst, J.D. Pack, *Phys. Rev. B* 13 (1976) 5188.
- [31] F. Averdunk, R. Hoppe, *J. Less-Common. Met.* 161 (1990) 135.
- [32] R.F. Li, S.Q. Wu, Y. Yang, Z.Z. Zhu, *J. Phys. Chem. C* 114 (2010) 16813.
- [33] G. Valerio, M. Catti, R. Dovesi, R. Orlando, *Phys. Rev. B* 52 (1995) 2422.